

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: Cher Huan TAN et al.

Serial No.: 10/025,085

Filed: December 19, 2001

For: Method For Preventing
Photoresist Poisoning In
Semiconductor Fabrication

§ Confirmation No.: 4906

§ Group Art Unit: 2813

§ Examiner: T. S. Pham

§ Atty Docket No.: 2085-00600

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TECHNOLOGY CENTER 2800

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RESPONSE TO THE OFFICE ACTION MAILED NOVEMBER 5, 2002

Assistant Commissioner for Patents
Washington, D.C. 20231

Client Ref. No. IME-P002US/fmk
Date: April 3, 2003

Sir:

This paper is filed in response to the Office Action mailed November 5, 2002. The Examiner is requested to enter the following amendments and consider the accompanying remarks. Reconsideration is respectfully requested.

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